

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings of claims in the application:

**Listing of Claims:**

1. (Original) A method for preventing dopant leaching from a doped structural film during fabrication of a microelectromechanical system, the method comprising:

producing a microstructure that includes the doped structural film, sacrificial material, and metallic material by a combination of techniques selected from the group consisting of deposition, patterning, and etching;

dissolving the sacrificial material with a release solution, the release solution comprising a substance destructive to the sacrificial material and acting as an electrolyte to form a galvanic cell with the doped structural film and metallic material acting as electrodes; and

suppressing effects of the galvanic cell by including a nonionic detergent mixed in the release solution.

2.-42. (Canceled)